



Substitute Form PTO-1449

(Modified)

U.S. Department of Commerce
Patent and Trademark OfficeAttorney's Docket No.
17979-034US1Application No.
10/562,257**Information Disclosure Statement
by Applicant**

(Use several sheets if necessary)

Applicant
Shafer et al.Filing Date
December 4, 2006Group Art Unit
~~2621~~ 2873**U.S. Patent Documents**

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
W.C./	AA	2005/0248856	11/2005	Omura et al.			
	AB	2002/0163629	11/7/2002	Switkes et al.			
	AC	2004/0109237	6/10/2004	Epple et al.			
	AD	2007/0052936	3/8/2007	Philips			
	AE	6,809,794	10/26/2004	Sewell			
	AF	2004/0125351	7/1/2004	Krautschik			
	AG	5,446,591	08/29/1995	Medlock			
	AH	5,627,674	05/06/1997	Robb			
	AI	6,169,627	01/02/2001	Schuster			
	AJ	6,496,306	12/17/2002	Shafer et al.			
	AK	2002/0196533	12/26/2002	Shafer et al.			
	AL	2003/0224528	12/04/2003	Chiou et al.			
	AM	2004/0105170	06/03/2004	Krahmer et al.			
	AN	2005/0219707	10/6/2005	Schuster et al.			
	AO	2005/0225737	10/13/2005	Weissenreider et al.			
	AP	2006/0221582	10/5/2006	DeNies et al.			
	AQ	2005/0190455	9/1/2005	Rostalski et al.			
	AR	2005/0179877	8/18/2005	Mulkens et al.			
	AS	2003/0174408	9/18/2003	Rostalski et al.			
	AT	2005/0161644	7/28/2005	Zhang et al.			
	AU	2005/0117224	6/2/2005	Shafer et al.			
	AV	2005/074704	4/7/2005	Endo et al.			
	AW	2005/0068499	3/31/2005	Docdoc et al.			
	AX	2005/0024609	2/3/2005	De Smit et al.			
	AY	4,346,164	8/24/1982	Tabarelli et al.			
	AZ	4,890,903	1/2/1990	Treisman et al.			
	AAA	5,682,263	10/1997	Robb et al.			

Examiner Signature

Date Considered

EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Substitute Form PTO-1449 (Modified) Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office		Attorney's Docket No. 17979-034US1	Application No. 10/562,257
	Applicant Shafer et al.			
	Filing Date December 4, 2006		Group Art Unit 2621	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
W.C./	ABB	6,181,485	1/2001	He, Chuan			
	ACC	2005/0074704	4/7/2005	Endo et al.			
	ADD	2006/0187430	8/24/2006	Docdoc et al.			
	AEE	7,187,503	03/06/2007	Rostalski et al.			
	AFF	2006/0012885	01/19/2006	Beder et al.			
	AGG	2007/0091451	04/26/2007	Schuster			
	AHH	2007/0109659	05/17/2007	Rostalski et al.			
	AII	2005/0190435	09/01/2005	Shafer et al.			
	AJJ	2005/0225737	10/13/2005	Weissenrieder et al.			
	AKK	2007/0165198	07/19/2007	Kneer et al.			
	ALL	2006/0244938	11/02/2006	Schuster			
	AMM	2006/0066962	03/30/06	Totzeck et al.			
	ANN	2004/075895	04/22/2004	Jeng et al.			
	AOO	5,900,354	05/04/1999	Batchelder et al.			

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
W.C./	APP	EP 1 491 956	12/29/2004	EPO				
	AQQ	WO 2004/057589	7/8/2004	WIPO				
	ARR	WO 2004/107048	12/9/2004	WIPO			English abstract	
	ASS	JP 2000-58436	02/25/2000	Japan			X	
	ATT	WO 2001/50171	07/12/2001	WIPO			English abstract	
	AUU	WO 2002/093209	11/21/2002	WIPO			English abstract	
	AVV	WO 2005/059617	6/30/2005	WIPO				
	AWW	WO 2006/045748	5/4/2006	WIPO				
	AXX	WO 2005/006026	1/20/2005	WIPO				
	AYY	WO 2005/081067	9/1/2005	WIPO				

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

Substitute Form PTO-1449 (Modified) Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 17979-034US1	Application No. 10/562,257
	Applicant Shafer et al.		
	Filing Date December 4, 2006	Group Art Unit 2621	

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
W.C./	AZZ	WO 2005/059645	6/30/2005	WIPO				
	AAAA	WO 2005/059618	6/30/2005	WIPO				
	ABBB	WO 2004/019128	3/4/2004	WIPO				
	ACCC	WO 2005/031823	4/7/2005	WIPO				
	ADDD	EP 1522894	4/13/2005	EPO				
	AEEE	EP 1486827	12/15/2004	EPO				
	AFFF	EP 0023231	2/4/1981	EPO				
	AGGG	DD 221563	4/24/1985	Germany				
	AHHH	DD 224448	7/3/1985	Germany				
	AIII	EP 1420302	5/19/2004	EPO				
	AJJJ	EP 1524558	4/20/2005	EPO				
	AKKK	JP 07220990	8/18/1995	Japan			X	
	ALLL	JP10-228661	8/25/1998	Japan			English Abstract	
	AMMM	JP10-303114	11/13/1998	Japan			X	
	ANNN	EP 1 645 911	04/12/2006	EPO				
	AOOO	EP 1 557 721	07/25/2005	EPO				
	APPP	EP 1 489 462	12/22/2004	EPO				
↓	AQQQ	EP 1 630 616	03/01/2006	EPO				

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
W.C./	ARRR	Burnett et al., "High Index Materials for 193 nm immersion Lithography", International Symposium on Immersion & 157 nm Lithography, February 8, 2004, pp 3, figure 1.
	ASSS	Dammel et al., "193 nm Immersion Lithography - Taking the Plunge", Journal of Photopolymer Science and Technology, vol. 17 no. 4, pp 587-607 (2004).
	ATTT	Kawata et al., "Fabrication of 0.2mm Fine Patterns Using Optical Projection Lithography With an Oil Immersion Lens", Japanese Journal of Applied Physics, Japan Society of Applied Physics, Tokyo, Japan, vol. 31 no. 12B, Part 1, December 1, 1992, pp 4174-4177.
↓	AUUU	Owa et al., "Immersion Lithography; its Potential Performance Issues", Proceeding of the SPIE, SPIE, Bellingham, VA, vol. 5040 no. 1, February 28, 2003, pp 724-733.

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 17979-034US1	Application No. 10/562,257
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Shafer et al.	
		Filing Date December 4, 2006	Group Art Unit 2621

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
W.C./	AVVV	Lammers, "'Doped water' could extend 193-nm immersion litho," <i>EETimes Online</i> , http://www.eetimes.com/showArticle.jhtml?articleID=18310517 , 2 pages (January 28, 2004).
↓	AWWW	Saurei et al., "Design of an autofocus lens for VGA 1/4-inch CCD and CMOS sensors," <i>SPIE International Symposium: Optical Systems Design</i> , St. Etienne, France, 1 page (2003)
↓	AXXX	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", <i>Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena</i> , American Vacuum Society, New York, NY, Vol. 17, No. 6, November 1999 (199-11) pp 3306-3309.
↓	AYYY	Smith, Bruce, "Water-based 193nm Immersion Lithography", Online!, http://www.sematech.org/resources/litho/meetings/immersion/20040128/presentations/06%20rit20\$microstepper%20effortsSmith.pdf , (January 28, 2004).

Examiner Signature William Choi/	Date Considered 11/12/2007
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	